

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
David S. Pecora

Serial No.: 09/854,206

Filed: May 11, 2001

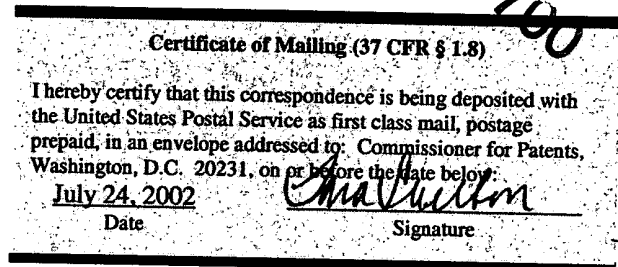
For: **ETCH OF SILICON NITRIDE SELECTIVE TO
SILICON AND SILICON DIOXIDE USEFUL
DURING THE FORMATION OF A
SEMICONDUCTOR DEVICE**



§
§ Group Art Unit: 1765
§
§ Examiner: Binh X. Tran
§
§ Atty. Docket: 00-0737.00/US
§
§ Paper No. 4
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Commissioner for Patents
Washington, D.C. 20231



Dear Sir:

INFORMATION DISCLOSURE STATEMENT

In compliance with the duty of disclosure under 37 CFR §1.56, Applicant respectfully requests that this Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. A copy of the reference is enclosed

In accordance with 37 CFR §1.97(b), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 CFR §1.56(a) exists.

The following reference is submitted for the Examiner's review:

U.S. Patent

U.S. Patent No.
5,580,821

Issue Date
12/1996

Inventor
Mathews et al.

08/01/2002 HMARZI1 00000096 133092 09854206
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Micron Technology, Inc.

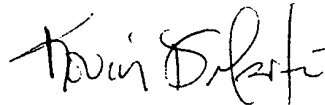
As this Information Disclosure Statement is being submitted after the mailing of a first Office Action on the merits, the Commissioner is authorized to charge the fee under 37 CFR 1.17(p), which is believed to be \$180, to Micron Technology Inc. Deposit Account No.13-3092, Order No. 00-0737.00.

If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicant's undersigned agent at the number indicated.

* * * *

A Form PTO-1449 is enclosed herewith.

Respectfully submitted,



Kevin D. Martin
Reg. No. 37,882
Micron Technology, Inc.
8000 S. Federal Way
Boise, ID 83716-9632
(208) 368-4516
Agent for Applicant